

EAST

L Number	Hits	Search Text	DB	Time stamp
1	36069	printing adj plate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 09:32
2	219	((printing adj plate) and ((etching and roughness) same (substrate or support or base)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:50
3	137	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (graining)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:09
4	131	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (anodization or anodizing or anodized)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:19
6	19	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (hydrophilization or wettability or wettability)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:20
7	144	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and electrochemical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:20
8	63	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and desmutting	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:19
10	2	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (surface adj gloss)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:15
5	1	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (curve near2 (peak or peaks))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 13:55
9	17	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:14
11	11	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:23
12	9	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting) and ((anodization or anodizing or anodized) and (graining))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:20
14	2	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting) and ((anodization or anodizing or anodized) and (graining))) and electrochemical) and (hydrophilization or wettability or wettability)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:20
13	9	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting) and ((anodization or anodizing or anodized) and (graining))) and electrochemical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:21
15	2	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting) not (((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting) and ((anodization or anodizing or anodized) and (graining))) and electrochemical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 10:24

16	9	((((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and honeycomb) and desmutting) and ((anodization or anodizing or anodized) and (graining))) and electrochemical) and alkali	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 12:21
18	176	((jis same roughness) and (printing adj plate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 12:21
19	141	((jis same roughness) and (printing adj plate)) and ((etching or roughness) same (substrate or support or base))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 12:23
20	9	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (curve same (peak or peaks))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:01
21	79	(printing adj plate) and (curve with (peak or peaks))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:04
22	8	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (curve with (peak or peaks))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:03
23	4	(printing adj plate) and (curve with (peak or peaks))	JPO	2003/01/23 14:04
24	8	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (surface with gloss)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:19
25	3	((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and ((surface with glossiness) or (gloss with meter))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:20
26	1	(((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and ((surface with glossiness) or (gloss with meter))) not (((printing adj plate) and ((etching and roughness) same (substrate or support or base))) and (surface with gloss))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:48
27	168	endo-tadashi\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:48
28	0	masuda-yoshitakai\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:48
29	133	nishino-atsuo\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:48
30	452	uesugi-akio\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:49
31	15	teraoka-katsuyuki\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:49
32	3	hotta-hisahi\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:49
35	37	uesugi-akio\$.in. and ((etching and roughness) same (substrate or support or base))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:58

36	1	teraoka-katsuyuki\$.in. and ((etching and roughness) same (substrate or support or base))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 15:04
34	13	nishino-atsuo\$.in. and ((etching and roughness) same (substrate or support or base))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:52
33	2	endo-tadashi\$.in. and ((etching and roughness) same (substrate or support or base))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:55
37	24	((uesugi-akio\$.in. and ((etching and roughness) same (substrate or support or base))) not (nishino-atsuo\$.in. and ((etching and roughness) same (substrate or support or base))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:58
38	24	((uesugi-akio\$.in. and ((etching and roughness) same (substrate or support or base))) not (nishino-atsuo\$.in. and ((etching and roughness) same (substrate or support or base)))) not (endo-tadashi\$.in. and ((etching and roughness) same (substrate or support or base)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/23 14:59